

STN 8 Caplus

(FILE 'HOME' ENTERED AT 19:33:21 ON 12 APR 2005)

FILE 'CAPLUS' ENTERED AT 19:33:27 ON 12 APR 2005

FILE 'CAPLUS' ENTERED AT 19:33:42 ON 12 APR 2005

L1 1323292 S ETCH? OR PATTERN? OR REMOV?
L2 1555963 S RESIST? OR PHOTORESIST? OR MASK? OR PHOTOMASK?
L3 31771 S SOI OR (SI ON INSULAT?) OR (SILICON ON INSULAT?) OR (SI ON SI
L4 1059012 S LAMINAT? OR BOND?
L5 637333 S WAFER? OR SEMICONDUCT? OR CHIP?
L6 114244 S GRIND? OR BEVEL? OR ABRAD? OR LAP?
L7 48 S L1 AND L2 AND L4 AND L5 AND L6
L8 56351 S L1(10A)L2
L9 919 S L8 AND L3
L10 651 S L5 AND L9
L11 9 S L6 AND L10
L12 51 S L7 OR L11
L13 5623 S L6 AND (?POLISH? OR CHEMIMECH? OR CMP)
L14 55 S L10 AND (?POLISH? OR CHEMIMECH? OR CMP)
L15 51 S L14 NOT L12
L16 129919 S RESIST OR PHOTORESIST OR MASK OR PHOTOMASK

L17 37493 S L16(10A)L1
L18 654 S L17 AND L3
L19 616 S L18 NOT (L7 OR L11 OR L14)
L20 2 S L19 AND L6
L21 9 S L19 AND (?POLISH? OR CHEMIMECH? OR CMP)
L22 11 S L20 OR L21
L23 3 S L18 AND BEVEL?
L24 0 S L23 NOT (L7 OR L11 OR L14 OR L22)

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(FILE 'HOME' ENTERED AT 17:10:10 ON 12 APR 2005)

FILE 'CAPLUS' ENTERED AT 17:10:29 ON 12 APR 2005

L1 622108 S WAFER? OR SEMICONDUCTOR? OR CHIP?
L2 1323292 S ETCH? OR PATTERN? OR REMOV?
L3 1059012 S BOND? OR LAMINAT?
L4 114244 S GRIND? OR BEVEL? OR LAP? OR ABRAD?
L5 144748 S PHOTORESIST? OR MASK? OR PHOTOMASK? OR PHOTOMASK?
L6 6365 S L1(10A)L2(10A)L5

L7 20521 S L1(10A)L3
L8 198 S L6 AND L7
L9 10 S L4 AND L8
L10 188 S L8 NOT L9
L11 10 S L10 AND (SOI OR (SILICON ON INSULAT) OR (SILICON ON SILICON))
L12 178 S L10 NOT L11
L13 0 S L12 AND BEVEL?
L14 0 S L1 AND L2 AND L3 AND L4 AND L5
L15 29 S L1 AND L2 AND L3 AND L4 AND L5
L16 19 S L15 NOT (L9 OR L10)
L17 178 S L12 NOT L15
SAVE ETCHL17/A L17
L18 149 S L17 NOT PAD?
L19 149 S L7 AND L18
L20 149 S L6 AND L19
L21 0 S L4 AND L20